

PROCEEDINGS OF SPIE

Novel Patterning Technologies for Semiconductors, MEMS/NEMS and MOEMS 2020

Martha I. Sanchez
Eric M. Panning
Editors

24–27 February 2020
San Jose, California, United States

Sponsored and Published by
SPIE

Volume 11324

Proceedings of SPIE 0277-786X, V. 11324

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Novel Patterning Technologies for Semiconductors, MEMS/NEMS and MOEMS 2020,
edited by Martha I. Sanchez, Eric M. Panning, Proc. of SPIE Vol. 11324, 1132401
© 2020 SPIE · CCC code: 0277-786X/20/\$21 · doi: 10.1117/12.2570852

Proc. of SPIE Vol. 11324 1132401-1

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Author(s), "Title of Paper," in *Novel Patterning Technologies for Semiconductors, MEMS/NEMS and MOEMS 2020*, edited by Martha I. Sanchez, Eric M. Panning, Proceedings of SPIE Vol. 11324 (SPIE, Bellingham, WA, 2020) Seven-digit Article CID Number.

ISSN: 0277-786X
ISSN: 1996-756X (electronic)

ISBN: 9781510634152
ISBN: 9781510634169 (electronic)

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

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